

M asuring System of a Gas Stream Environment

ABSTRACT OF THE INVENTION

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This invention relates to a measuring system, more particularly, to a measuring system of a gas stream environment to measure the thickness of the wafer successfully and accurately. The gas stream environmental measuring system comprises a monitor, a stage, a lens, 10 the first gas nozzle, a gas supplier, the second gas nozzle, a transport slot, a gas-extracting apparatus, a transport device, the first flow rate regulating valve, the second flow rate regulating valve, the first tube, the second tube, the third tube, a datum platen, and a datum slice. Using the gas stream, which is formed by using the gas exhausted from the 15 first gas nozzle and the second gas nozzle to the wafer and the measuring reference point, makes the gas, which evaporates from the wafer, flow with the gas stream and flow to the outside of the measuring system by using the transport slot and the gas-extracting apparatus to measure the thickness of the wafer successfully and accurately.

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